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(Not for submission under 37 CFR 1.99)

Application Number	10717028
Filing Date	2003-11-18
First Named Inventor	Nancy Iwamoto
Art Unit	1752
Examiner Name	Connie P. Johnson
Attorney Docket Number	H0005567.36146 - 4780

U.S. PATENTS

Examiner Initial*	Cite No	Patent Number	Kind Code†	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
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	2	4299938		1981-11-10	Ciba-Geigy Corporation	
	3	4413052		1983-11-01	Ciba-Geigy Corporation	
	4	4430153		1984-02-07	International Business Machines Corporation	
	5	4587138		1986-05-06	Intel Corporation	
	6	4863827		1989-09-05	American Hoechst Corporation	
	7	4863829		1989-09-05	Sumitomo Chemical Company, Limited	
	8	4910122		1999-03-20	Brewer Science, Inc.	

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9	4935583		1990-06-19	Kyle, James C.	
10	4943511		1990-07-24	Morton Thiokol, Inc.	
11	4950583		1990-08-21	Brewer Science Inc.	
12	5100503		1992-03-31	NCR Corporation	
13	5126289		1992-06-30	AT&T Bell Laboratories	
14	5302849		1994-04-12	Motorola, Inc.	
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16	5759625		1998-06-02	E. I. du Pont de Nemours and Company	
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19	6165697		2000-12-26	Shipley Company, L.L.C.	

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	20	6451503	B1	2002-09-17	Shipley Company, L.L.C.	
	21	6472128	B2	2002-10-29	Shipley Company, L.L.C.	
	22	6528235	B2	2003-02-04	Shipley Company, L.L.C.	
	23	7014982	B2	2006-03-21	Shipley Company, L.L.C.	
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	25	5674648	A	1997-10-07	Brewer et al.	
	26	4191571		1980-03-04	Nonogaki et al.	

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U.S. PATENT APPLICATION PUBLICATIONS

Examiner Initial*	Cite No	Publication Number	Kind Code ¹	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
	1	20060110682	A1	2006-05-25	Shipley Company, L.L.C.	
	2	20060155594	A1	2006-07-13	Jess Almeida, et al.	

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FOREIGN PATENT DOCUMENTS

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	1	Brewer, T. et al., "The Reduction of the Standing Wave Effect in Positive Photoresists," Jour. Appl. Photogr. Eng., Vol. 7, no. 6, 184-186 (Dec. 1981).	<input type="checkbox"/>
	2	Crivello et al., J. Polym. Sci.: Polym. Chem. 21 (1983), 97-109.	<input type="checkbox"/>
	3	Degussa, "Silanes for Adhesives and Sealants," 18-19, available at www.dynasylan.com .	<input type="checkbox"/>
	4	Lamola, A. et al., "Chemically Amplified Resists," Solid State Technology, 53-60 (August 1991).	<input type="checkbox"/>
	5	Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," Advances in Resist Technology and Processing, Proc., SPIE vol. 469, 30-37 (1984).	<input type="checkbox"/>
	6	McKean et al., "Characterization of a Novolac-Based Three-Component Deep-UV Resist," Chem. Mater. (1990) 2, 619-624.	<input type="checkbox"/>
	7	Nalamasu et al., "Development of a Chemically Amplified Positive (CAMP) Resist Material for Single Layer Deep-UV Lithography," Advances in Resist Technology and Processing VII, SPIE 1262, 32-41 (1990).	<input type="checkbox"/>

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8	Silverstein et al., "Spectrometric Identification of Organic Compounds," 4th Ed. John Wiley & Sons 1991, 309-311.	<input type="checkbox"/>
9	Willson, C.G., "Organic Resist Materials - Theory and Chemistry," Introduction to Microlithography, American Chemical Society, 87-159 (1983).	<input type="checkbox"/>
10	Hawley's Condensed Chemical Dictionary, 11th ed., 85-86.	<input type="checkbox"/>
11	"HD Micro Puts Out Positive Polyamide," Electronic News, June 19, 2000.	<input type="checkbox"/>
12	Jaskot et al., Toxicological Sciences, 22(1): 103-112 (1994).	<input type="checkbox"/>
13	Yusuke Izumi, et al., "Hydrosilylation of Carbonyl Compounds Catalyzed by Solid Acids and Bases," Tetrahedron Letters, Vol. 32, No. 36, pp 4744 (1991).	<input type="checkbox"/>

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